

## IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

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**EXAMINER:** G. Peralta

**TITLE:** Random Access Memory

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## AMENDMENT ACCOMPANYING REQUEST FOR CONTINUED EXAMINATION

## Amendments to the Claims

- 23.(currently amended) A semiconductor memory device, comprising:
- a silicon structure having a first conductivity type;
- a gate electrode over the silicon structure;
- a capacitor contact region in the silicon structure adjacent to one side of the gate electrode;
- a bit line contact region in the silicon structure adjacent to the other side of the gate electrode;
- a first dopant implant in the capacitor and bit line contact regions, the first dopant having a second conductivity type opposite the first conductivity type and the first dopant implant physically contacting the capacitor contact region; and
  - a second dopant implant in only the capacitor contact region.
- 24.(original) A device according to Claim 23, wherein the second dopant implant is deeper than the first dopant implant.